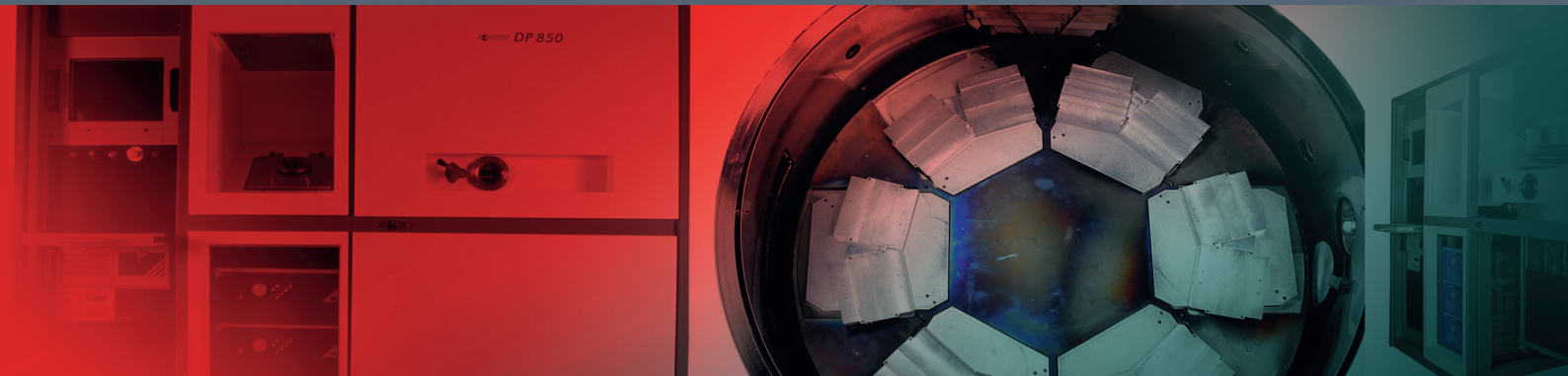


Vacuum ▶ PVD Thin films ▶ Leak testing ▶ Plasma



Multi-cathode system for vacuum coating

DP 850



by
allianceconcept

Design for large volume and top quality production

The DP850 system is oriented towards production tasks. With a source configuration with up to 6 x 200 mm magnetron cathodes, it enables the manufacturing of complex multilayers in automatic mode.

The load lock optimizes time cycle and quality of the deposited films.

We also adapt the DP850 systems and their 850 mm vacuum chamber diameter for research applications that require a source configuration with more than 10 x 2" cathodes.



Main features

Vacuum chamber diameter :	850 mm
Height :	320 mm
Volume :	About 190 litres
Ultimate vacuum (turbomolecular configuration) :	5.10^{-7} mbar ^[1]
Ultimate vacuum (cryogenic configuration) :	5.10^{-8} mbar ^[1]
System throughput :	6 active 100 mm positions
Planar configuration uniformity :	< +/- 5% ^[1]
Through the wall installation :	Yes
Load lock :	Yes
Fully automatic system controller :	- Process management - Traceability

^[1] These values have been measured on equipment we have delivered and should be handled as information only. The features of a system depend on its final configuration.

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